

18. (Amended) A method for manufacturing an electro-optical device comprising:
a step of forming a molecular film pattern according to a method for manufacturing a molecular film pattern recited in Claim 1.
22. (Amended) A method for manufacturing an electronic device comprising:
a step performed by using a method for manufacturing a molecular film pattern recited in Claim 1.
23. (Amended) An electronic apparatus comprising an electro-optical device according to Claim 19 as a display portion.

REMARKS

Claims 1-23 are pending. By this Preliminary Amendment, claims 12-16, 18, 22 and 23 are amended to remove multiple dependencies. Prompt and favorable examination on the merits is respectfully requested.

The attached Appendix includes marked-up copies of each rewritten claim (37 C.F.R. 1.121(c)(1)(ii)).

Respectfully submitted,

James A. Oliff
Registration No. 27,075

Eric D. Morehouse
Registration No. 38,565

JAO:EDM/gam

Attachment:
Appendix

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OLIFF & BERRIDGE, PLC
P.O. Box 19928
Alexandria, Virginia 22320
Telephone: (703) 836-6400

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APPENDIX

Changes to Claims:

The following are marked-up versions of the amended claims:

12. (Amended) A method for manufacturing a molecular film pattern according to ~~one of~~ Claims 3, 4, 5, 6, 9, 10, and 11,

wherein R¹ of the organic silicon compound is a perfluoroalkyl group.

13. (Amended) A method for manufacturing a molecular film pattern according to ~~one of~~ Claims 3, 4, 5, 6, 9, 10, and 11,

wherein R¹ of the organic silicon compound is a trifluoromethyl group.

14. (Amended) A method for manufacturing a molecular film pattern according to ~~one of~~ Claims 1 ~~to~~ 13,

wherein the thickness of the molecular film is 3 nm or less.

15. (Amended) A molecular film pattern formed by a method for manufacturing a molecular film pattern according to ~~one of~~ Claims 1 ~~to~~ 14.

16. (Amended) A method for manufacturing a semiconductor device comprising:
a step of forming a molecular film pattern according to a method for manufacturing a molecular film pattern recited in ~~one of~~ Claims 1 ~~to~~ 14.

18. (Amended) A method for manufacturing an electro-optical device comprising:

a step of forming a molecular film pattern according to a method for manufacturing a molecular film pattern recited in ~~one of~~ Claims 1 ~~to~~ 14.

22. (Amended) A method for manufacturing an electronic device comprising:
a step performed by using a method for manufacturing a molecular film pattern recited in ~~one of~~ Claims 1 ~~to~~ 14.

23. (Amended) An electronic apparatus comprising an electro-optical device according to Claim 19 ~~or~~ 21 as a display portion.